

## REMARKS

The Examiner has provided a further restriction in this case, particularly the tension between claims 8 versus claim 9, where claim 8 requires the presence of one or more of the oligomeric and/or (co)polymeric chelators attached to the particle which are poly(styrene sulfonic acid), poly(vinyl sulfonic acid), poly(acrylic acid), poly(methacrylic acid), a poly(acrylate), a poly(methacrylate), a poly(alkacrylate), poly(maleic acid), poly(vinyl acetate), poly(vinyl alcohol), poly(acrylamide), poly(cyanoacrylate), a cellulosic material, or a mixture or copolymer thereof, and claim 9 cites the chelators are not these poly(functional) polymers.

Applicants elect claim 9 for examination.

The Examiner in the restriction requirement grouped claims 8 and 22 together, and Applicants believe this was in error. Claim 22 depends from claim 15, but claim 22 adds nothing to the recitations of claim 15 relative to the oligomeric or polymeric chelators of claim 15. The main thrust of claim 22 is the oligomeric and/or (co)polymeric chelating agent of claim 15 is attached to the particle by a covalent chemical bond. Applicants note that previously presented Claim 15 recites that the chelator particle is a particle body and a polymer or a oligomer or copolymer having a plurality of pendant functional groups comprising hydroxyls, carboxylic acids, sulfonic acids, and/or others. Applicants deleted the phrase oligomer or copolymer from claim 15, but not for example that a polymer or copolymer having a plurality of sulfonic acid functional groups thereon is not necessarily a poly(styrene sulfonic acid), and a polymer or copolymer having a plurality of carboxylic acid functional groups thereon is not necessarily a poly(acrylate).

In view of the Examiner's restrictions, Applicants were concerned that the Examiner might not be focusing on an important embodiment of the invention. Applicants have further limited independent claims 14 and 15 to bring this particular important embodiment to the forefront of the Examiner's attention, by incorporating several of the "spacer" recitations in dependent claim 11 therein. The key to applicant's invention is the tenacity and reproducibility of having the chelating agents remaining attached to particles during polishing. As described in

paragraph [0036], a spacer can allow the formation of a stronger bond (e.g., a covalent bond) between the particle surface and the chelator.

Applicants reserve the rights to pursue claims not reciting a spacer in subsequent continuations and divisional applications.

Applicants would like to remind the Examiner that the customer number for this application has been changed, as noted on the Request for Address Correction filed on December 27, 2005.

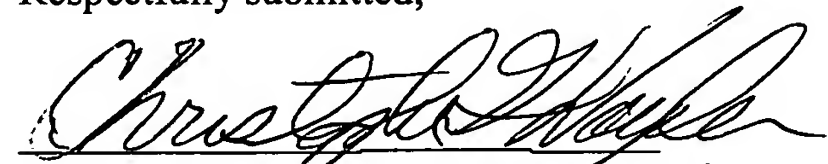
Reconsideration and allowance is respectfully requested.

No fee is believed due for the submission of this Response; however, please charge any required fee, and any other fees or credits, to **Morgan, Lewis & Bockius LLP** Deposit Account No. 50-0310.

Respectfully submitted,

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